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Subdiffraction-limited Plasmonic Lithography and Innovative Manufacturing Technology

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Contents

vii	<i>Authors</i>
xi	<i>Symposium Committees</i>
xiii	<i>AOMATT 2018 Sponsors</i>

SUBDIFFRACTION-LIMITED PLASMONIC LITHOGRAPHY AND INNOVATIVE MANUFACTURING TECHNOLOGY

10842 02	A Hermitian symmetry based OFDM signal transmitter for digitized radio-over-fiber transmission [10842-1]
10842 03	Research on temperature distribution and thermal stress of laser crystal from self-Raman yellow laser [10842-2]
10842 04	Negative capacitance transistors with sub-kT/q swing [10842-3]
10842 05	Feature extraction of acoustic emission signals in diamond scratching of brittle materials based on shift-invariant sparse coding [10842-5]
10842 06	An experimental platform for rapid melting and solidification of metal materials in space [10842-6]
10842 08	3D printing of hypothetical brick by selective laser sintering using lunar regolith simulant and ilmenite powders [10842-9]
10842 09	Controllable wettability of metallic surfaces via micro-nano structure fabricated by femtosecond laser [10842-10]
10842 0A	Analysis on the evolution of subwavelength ripples fabricated by ultrafast laser pulses on lithium niobate crystal surface [10842-11]
10842 0B	Additive manufacturing of millimeter-scale micron-accuracy 3D structures [10842-12]
10842 0C	Biocompatible three-dimensional hydrogel microstructures fabricated by two-photon polymerization [10842-13]
10842 0D	The luminance measurement model of LED display using the image sensors [10842-15]
10842 0E	Three-dimensional micro-cones fabricated via two-photon photolithography [10842-16]
10842 0F	Surfactant mediated synthesis of structured metal nanoparticle by pulsed laser ablation for photocatalysis [10842-17]
10842 0G	Multi-photon laser lithography of AR-N 4340 photoresist with a spatial resolution at nanoscale [10842-19]

- 10842 0H **Structural modifications induced by ultrafast IR laser pulses in sapphire** [10842-20]
- 10842 0I **Structural modeling and strength characteristics of optical system in strong impact environment** [10842-21]
- 10842 0J **Integration of functional microstructures inside a microfluidic chip by direct femtosecond laser writing** [10842-22]
- 10842 0K **Investigation on the nonlinear relationship between relative velocity and material removal in bonnet polishing** [10842-23]
- 10842 0L **Advanced metal-wire laser additive manufacturing in-space** [10842-24]
- 10842 0M **Research on hand-eye calibration method based on stereo vision for harvesting robot** [10842-25]
- 10842 0N **Fabrication of superhydrophobic magnesium alloy surface for water repellent** [10842-26]
- 10842 0O **Liquid bridge simulation of metal-wire laser additive manufacturing in microgravity environment** [10842-27]
- 10842 0P **A true-color nano-CT based on SEM** [10842-33]
- 10842 0Q **A high-precision optical fiber adaptive lithography method for vertical integration of optical fiber and planar chip** [10842-38]
- 10842 0R **Large area transparent organic light-emitting device by using PFN modified ZnO as electron transfer layer** [10842-52]
- 10842 0S **Ion beam figuring high gradient optical aspherical surface** [10842-53]
- 10842 0T **Organic-inorganic hybrid perovskite photodetectors achieved via brush-coating process** [10842-57]
- 10842 0U **Relationship between slurry flow pattern and removal characteristic based on a novel polishing tool** [10842-70]
- 10842 0V **Computer-aided NC programming system for large scale and off-axis aspheric optics in parallel grinding** [10842-72]
- 10842 0W **Parameters selection for different metals in coating thickness measurement using x-ray fluorescence analysis** [10842-77]
- 10842 0X **Fabrication and optical properties of Er-doped ZnO thin films** [10842-78]
- 10842 0Y **Influence of liquid crystal alignment material and technology on phase modulation of liquid crystal microwave phase shifter** [10842-79]
- 10842 0Z **Damage resistance of fused silica modified by magnetorheological finishing (MRF) and ion beam etching (IBE)** [10842-91]

- 10842 10 **Enhancing the wettability of PEDOT:PSS layer with plasma treatment method in perovskite solar cells** [10842-99]
- 10842 11 **Fabrication of small cylindrical lens** [10842-111]
- 10842 12 **Precision manufacturing technology of axicon** [10842-120]
- 10842 13 **Laser generation of ultrasound in adhesively bonded three-layered plate** [10842-123]
- 10842 14 **Ultra-precision robotic sub-aperture polishing of curved mirrors** [10842-137]
- 10842 15 **Enhancing performance of inverted organic solar cells by nano-imprinting the active layer with a PDMS template** [10842-150]
- 10842 16 **Study of optic and laser-induced damage properties of Ta₂O₅ films deposited by different process parameters** [10842-216]
- 10842 17 **A preliminary study of in-situ defects measurement for additive manufacturing based on multi-spectrum** [10842-225]
- 10842 18 **Kilo-joule back lighting terminal system** [10842-261]
- 10842 19 **Analysis of computer-generated holographic microstructure fabricated by femtosecond laser** [10842-299]
- 10842 1A **Near field optical lithography using ultra-small gap bowtie apertures** [10842-503]
- 10842 1B **Design of bifocal compound eyes and gray mask fabrication based on maskless photolithography** [10842-508]
- 10842 1C **Double-beam laser interference lithography based on optical field modulation** [10842-521]
- 10842 1D **Fabrication of porous structures on microchannel surfaces by laser micromilling for enhanced microchannel heat sinks** [10842-08]

Authors

Numbers in the index correspond to the last two digits of the seven-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first five digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Amina, 0H
Bi, Guo, 05
Cao, Hong-Zhong, 06, 08, 0G
Cao, Jun, 12
Cao, Kuo, 10
Cao, Mengyao, 0A
Chai, Xiangxu, 18
Chen, Dengling, 0K
Chen, Jiechang, 0D
Chen, Liang, 1D
Chen, Tian, 09
Chen, Xian-hua, 0U
Chen, Xianhua, 0Z
Chen, Xiaolong, 1D
Chen, Yao, 17
Cui, Jingqin, 0F
Cui, Yanxia, 15
Dai, Zuocai, 19
Deng, Daxiang, 1D
Deng, Qingyuan, 1B
Deng, Weijie, 0S
Deng, Wenhui, 0Z
Ding, Leiming, 0M
Ding, Xueping, 06, 0L, 0O
Dong, Huaiyuan, 0T
Dong, Xian-Zi, 0B, 0C, 0E, 0G
Du, Farui, 0L
Du, Hua, 0W
Duan, Xuan-Ming, 06, 08, 09, 0B, 0E, 0G, 0L, 0O
Dun, Aihuan, 12
Fan, Shuqian, 06, 09, 0L, 0O
Feng, Bin, 18
Gan, Zihao, 19
Guan, Chaoliang, 19
Guo, Rui, 11
Guo, Yi, 02
Guo, Yinbiao, 0K
Han, Genquan, 04
Han, Li, 0P
Han, Yu, 0X
Hao, Yang, 15
Hao, Yue, 04
Hao, Yuying, 15
Hou, Jing, 0Z
Hou, Liang, 0K
Hu, Kai, 0J
Hu, Song, 1B
Hu, Yanlei, 0J
Hu, Yingru, 0Y
Hu, Zhijiang, 0J
Hua, Xiaobin, 0I
Huang, Jiang, 0T
Huang, Shuai, 0N
Huang, Xiaona, 10
Ji, Lingfei, 0H
Ji, Ting, 15
Ji, Yunjing, 0I
Jiang, Rui, 0M
Jin, Feng, 0B, 0C, 0E, 0G
Jing, Yukun, 18
Kang, Jian-yun, 05
Kong, Lingbao, 17
Lai, Jiancheng, 0I
Li, Chenlei, 0K
Li, Fanxing, 1C
Li, Houjun, 16
Li, Jing, 04
Li, Mian, 16
Li, Peng, 02
Li, Peng, 0Y
Li, Peng, 18
Li, Qiang, 0A
Li, Wangwang, 0Q
Li, Xiaoguang, 0F
Li, Xiaojie, 0N
Li, Xiongyao, 08
Li, Yaguo, 0Z
Li, Yanan, 0A
Li, Zhenhua, 0I
Li, Zhixuan, 0A
Liang, Ting, 0Q
Lin, Chun, 0F
Liu, Bin, 03
Liu, Dongbing, 18
Liu, Jiajin, 0Y
Liu, Jianghui, 1B
Liu, Jianzhong, 08
Liu, Jie, 0B, 0C, 0E
Liu, Junbiao, 0P
Liu, Junbo, 1B
Liu, Xuanmin, 11
Liu, Yan, 04
Liu, Yijie, 0F
Liu, Yufan, 0R
Liu, Yu-Huan, 0E
Lu, Pin, 0M
Luo, Bin, 02
Luo, Hu, 0N

Ma, Honglin, 06, 08
Ma, Yutian, 0P
Niu, Geng, 0P
Pan, Wei, 02
Peng, Fuping, 1C
Peng, Siping, 14
Peng, Xiaoqiang, 19
Peng, Xing, 17
Peng, Xuhui, 0Y
Peng, Yue, 04
Peng, Yunfeng, 05, 0K
Qin, Jin, 1A
Qiu, Kaifang, 15
Rong, Jie, 0W
Shao, Jianda, 12
Shao, Junze, 10
Shi, Chenchun, 0K
Shi, Linlin, 15
Song, Lei, 08
Su, Jun-hong, 16
Su, Ying, 11
Sun, Bingyu, 0M
Sun, Xiaoyong, 08
Tang, Hong, 08
Tang, Qilin, 0K
Tang, Qingchun, 0N
Tang, Wa, 0S
Tang, Yan, 1B
Uzair, Muhammad, 0H
Wan, Songlin, 14
Wang, Chunyong, 0I
Wang, Guanzong, 18
Wang, Guoyu, 06, 0L, 0O
Wang, Hui-xue, 05
Wang, J., 0V
Wang, Jian, 0Z
Wang, Jian, 16
Wang, Junhua, 17
Wang, Kai, 0W
Wang, Lei, 0D
Wang, Liang, 1A
Wang, Liquan, 18
Wang, Mingzhu, 10
Wang, Rujing, 0M
Wang, Wenqiang, 0M
Wang, Yan, 0P
Wang, Zhenzhong, 0K
Wei, Q. C., 0V
Wen, Zhong-jiang, 0U
Wu, Bo, 0Y
Wu, Dong, 0J
Wu, Fulin, 12
Wu, Hao, 0J
Wu, Mengge, 0R
Wu, Qiang, 0A
Wu, Wen Jie, 09
Wu, Xishan, 03
Xiang, Siheng, 0T
Xie, Haiqiong, 0O
Xie, Xudong, 18

Xie, Yanlin, 1D
Xin, Chen, 0J
Xu, Bing, 0J
Xu, Haiming, 0M
Xu, Jiao, 08
Xu, Jing-hua, 0X
Xu, Jingjun, 0A
Xu, Jun-qj, 16
Xu, Min, 14, 17
Xu, Q., 0V
Xu, Tao-lin, 05
Xu, Xueke, 12
Xu, Zengqi, 11
Yan, Huangping, 0F
Yan, Lianshan, 02
Yan, Tianyang, 0H
Yan, Wei, 0I
Yan, Wei, 1C
Yan, Yafei, 0M
Yan, Yang, 03
Yang, Fan, 1C
Yang, Haicheng, 11
Yang, Hua, 0B
Yang, Jie, 06
Yang, Liang, 06, 09
Yang, Liang, 0J
Yang, Qin, 09
Yang, Qingguo, 18
Yao, Jianghong, 0A
Ye, Jia, 02
Yin, Shaohui, 0N
Yin, Xiaolin, 0S
Yin, Yuanchao, 0F
Yu, He, 10
Yu, Hong, 0C
Yu, Junsheng, 0R
Yu, Miao, 10
Yuan, Zhigang, 0Z
Zhang, Chenchu, 0J
Zhang, Chunling, 0A
Zhang, Feng, 11
Zhang, Jincheng, 04
Zhang, Peng, 03
Zhang, Q. H., 0V
Zhang, Qi, 06, 0L
Zhang, Ruoyu, 10
Zhang, Wanli, 10
Zhang, Xiangchao, 14
Zhang, Yanchao, 12
Zhang, Yang, 10
Zhang, Yonggang, 0F
Zhang, Yu, 11
Zhang, Zhengyong, 0M
Zhao, Dan, 0R
Zhao, Danyang, 0M
Zhao, S. J., 0V
Zhao, Weixia, 0P
Zhao, Yan, 13
Zhao, Yuan-Yuan, 0B, 0C, 0E
Zhao, Zhen-Sheng, 0B, 0E, 0G

Zheng, Mei-Ling, 0B, 0C, 0E, 0G
Zheng, Peng, 0D
Zhong, Bo, 0U
Zhong, Hongmei, 0J
Zhou, Jinsong, 14
Zhou, Jiuren, 04
Zhou, L., 0V
Zhou, Rui, 0D, 0F
Zhu, Deyan, 18
Zhu, Furong, 15
Zhu, Xiaoping, 0W

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